

# Kenta Suzuki

## List of Publications by Year in descending order

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37  
papers

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citations

1307594

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37  
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docs citations

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times ranked

72  
citing authors

#	ARTICLE	IF	CITATIONS
1	Flexible Polyimide Micropump Fabricated Using Hot Embossing. Japanese Journal of Applied Physics, 2011, 50, 06GM09.	1.5	16
2	Flexible Polyimide Micropump Fabricated Using Hot Embossing. Japanese Journal of Applied Physics, 2011, 50, 06GM09.	1.5	15
3	Study on Change in UV Nanoimprint Pattern by Altering Shrinkage of UV Curable Resin. Japanese Journal of Applied Physics, 2011, 50, 06GK09.	1.5	13
4	Bubble-free patterning with low line edge roughness by ultraviolet nanoimprinting using trans-1,3,3,3-tetrafluoropropene condensable gas. Applied Physics Letters, 2016, 109, .	3.3	10
5	Throughput of Ultraviolet Nanoimprint in Pentafluoropropane Using Spin Coat Films under Thin Residual Layer Conditions. Japanese Journal of Applied Physics, 2012, 51, 06FJ10.	1.5	9
6	Transfer of Relatively Large Microstructures on Polyimide Films using Thermal Nanoimprinting. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2012, 25, 255-260.	0.3	9
7	Effective Linewidth Measurement of 45-nm-Half-Pitch Ultraviolet Nanoimprint Lithography Patterns by Scanning Electron Microscope Inspection and Extremely Shallow Si Etching. Japanese Journal of Applied Physics, 2012, 51, 06FJ09.	1.5	8
8	Control of Resin Filling and Pattern Quality of Ultraviolet Nanoimprint Lithography in Pentafluoropropane and Helium Ambient. Japanese Journal of Applied Physics, 2013, 52, 06GJ07.	1.5	7
9	In-situ Evaluation of Air/Oxygen Percentage Variation by Introducing 1,1,1,3,3-Pentafluoropropane in Ultraviolet Nanoimprint Lithography. Japanese Journal of Applied Physics, 2012, 51, 118002.	1.5	7
10	Bubble-free high-speed UV nanoimprint lithography using condensable gas with very low global warming potential. Japanese Journal of Applied Physics, 2016, 55, 076502.	1.5	6
11	Filling Behavior and Mold Release Force in UV Nanoimprinting Using PDMS Mold in Different Atmosphere. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2018, 31, 295-300.	0.3	6
12	Uniform Residual Layer Creation in Ultraviolet Nanoimprint Using Spin Coat Films for Sub-100-nm Patterns with Various Pattern Densities. Japanese Journal of Applied Physics, 2013, 52, 06GJ06.	1.5	5
13	In-situ Evaluation of Air/Oxygen Percentage Variation by Introducing 1,1,1,3,3-Pentafluoropropane in Ultraviolet Nanoimprint Lithography. Japanese Journal of Applied Physics, 2012, 51, 118002.	1.5	4
14	Fabrication of sub 20-nm wide grooves in a quartz mold by space narrowing dry etching. Microelectronic Engineering, 2013, 110, 432-435.	2.4	4
15	Cu/Polyimide Multilayer Interconnections Fabricated by Nanoimprint at Every Lithography Process. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2014, 27, 73-80.	0.3	4
16	Nano-patterning on soluble block copolymer polyimide by nanoimprint. Japanese Journal of Applied Physics, 2015, 54, 088002.	1.5	4
17	Ultraviolet Nanoimprint Lithography in the Mixture of Condensable Gases with Different Vapor Pressures. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2016, 29, 181-187.	0.3	4
18	Throughput of Ultraviolet Nanoimprint in Pentafluoropropane Using Spin Coat Films under Thin Residual Layer Conditions. Japanese Journal of Applied Physics, 2012, 51, 06FJ10.	1.5	4

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19	Real-time full-area monitoring of the filling process in molds for UV nanoimprint lithography using dark field illumination. <i>Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics</i> , 2012, 30, 06FB13.	1.2	3
20	Simple fabrication process for UV nanoimprint mold with embedded metal alignment marks for in-liquid alignment. <i>Japanese Journal of Applied Physics</i> , 2014, 53, 06JK01.	1.5	3
21	Selective Cu Patterning on Polyimide Using UV Surface Treatment and Electroless Plating. <i>Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]</i> , 2015, 28, 157-161.	0.3	3
22	Chip-scale pattern modification method for equalizing residual layer thickness in nanoimprint lithography. <i>Japanese Journal of Applied Physics</i> , 2018, 57, 06HG03.	1.5	3
23	Effects of Granularity of Complementary Patterns in a Capacity-Equalized Mold Used for UV Nanoimprint Lithography. <i>Japanese Journal of Applied Physics</i> , 2011, 50, 06GK08.	1.5	2
24	Ring-Shaped Silicon Resonator Using (2,1) In-Plane Resonance Mode. <i>Applied Mechanics and Materials</i> , 0, 189, 274-280.	0.2	2
25	Pt Nanogap Electrode Fabrication by Two-Layer Lift-Off UV-NIL and Nanowire Breakdown. <i>IEEE Nanotechnology Magazine</i> , 2018, 17, 1094-1097.	2.0	2
26	Solubility Property of Condensable Gases of Trans-1-Chloro-3,3,3-Trifluoropropene and Trans-1,3,3,3-Tetrafluoropropene in UV Nanoimprint. <i>Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]</i> , 2019, 32, 123-130.	0.3	2
27	Fabrication Processes for Capacity-Equalized Mold with Fine Patterns. <i>Japanese Journal of Applied Physics</i> , 2011, 50, 06GK04.	1.5	1
28	Study on Quartz Multitier Mold Fabrication Using Gray Scale Laser Beam Lithography. <i>Japanese Journal of Applied Physics</i> , 2011, 50, 06GK03.	1.5	1
29	Effective Linewidth Measurement of 45-nm-Half-Pitch Ultraviolet Nanoimprint Lithography Patterns by Scanning Electron Microscope Inspection and Extremely Shallow Si Etching. <i>Japanese Journal of Applied Physics</i> , 2012, 51, 06FJ09.	1.5	1
30	Resin filling of UV-cured nanoimprints using pentafluoropropane to fabricate large patterns with a thin residual layer. <i>Microelectronic Engineering</i> , 2015, 136, 81-84.	2.4	1
31	Evaluation of Nanoimprinting Multilayer Lift-off Process using Spin-on-glass for Nanogap Electrode Array. <i>Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]</i> , 2018, 31, 277-282.	0.3	1
32	Basic Verification of Method for Automated Design of Capacity-Equalized Mold for Nanoimprint Lithography. <i>Journal of Nanoscience and Nanotechnology</i> , 2017, 17, 8475-8479.	0.9	1
33	MEMS Tilt Sensor Fabricated Utilizing Anodic Bonding of Thin Silicon Film on Glass Substrate. <i>IEEJ Transactions on Sensors and Micromachines</i> , 2009, 129, 328-332.	0.1	1
34	Freely Expandable Single Crystalline Si Networks for MEMS Applications. <i>IEEJ Transactions on Sensors and Micromachines</i> , 2010, 130, 130-134.	0.1	1
35	Improved Performances of All-Polyimide Fluidic Devices Using Thermal Nanoimprinting. <i>Applied Mechanics and Materials</i> , 2013, 300-301, 1360-1363.	0.2	0
36	Fabrication of high-aspect-ratio micropatterns in soluble block-copolymer polyimides by a UV-assisted thermal imprint process. <i>Journal of Mechanical Science and Technology</i> , 2019, 33, 3755-3760.	1.5	0

#	ARTICLE	IF	CITATIONS
37	Mold Design and Process for Application of Nanoimprint Lithography to Interconnections. Journal of Japan Institute of Electronics Packaging, 2019, 22, 158-163.	0.1	0